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Atty Dkt No AMAT/4180/DSM/BCVD/JW

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

re Application of: Huang, et al

Serial No.: 09/902,518

Confirmation No.: 7428

Filed: July 10, 2001

For: Method and Apparatus for Treating

Low K Dielectric Layers to Reduce

Diffusion

Commissioner for Patents Washington, D.C. 20231

Group Art Unit: 28

2824

Examiner: Michael Lebentritt

And I -7-03
A. Wash

CERTIFICATE OF MAILING

37 CFR 1.8

I hereby certify that this correspondence is being deposited on <u>December 17, 2002</u> with the United States Postal Service as First Class Mail in an envelope addressed to: Commissioner for Patents, Washington, D.C. 20231.

12/17/2

Signature

Dear Sir:

RESPONSE TO OFFICE ACTION DATED SEPTEMBER 27, 2002

In response to the Office Action dated September 27, 2002, having a shortened statutory period for response set to expire on December 27, 2002, Applicant requests entry and consideration of the following amendments and remarks. The Commissioner is hereby authorized to charge counsel's Deposit Account No. 20-0782/AMAT/4180/DSM/BCVD/KMT, in the amount of \$156.00 for 1 additional independent claim and 4 total new claims, and any fees, including extension of time fees or excess claim fees, required to make this response timely and acceptable to the Office.

IN THE CLAIMS:

1.

Please cancel claims 3 and 26 without prejudice, and amend the claims as follows:

(Amended) A method for processing a substrate, comprising:

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